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INFORMATION	Atty. Docket No.: 150.00840102	Serial No.: 10/770,797
DISCLOSURE STATEMENT	Applicant(s): Yates et al.	Confirmation No.: Unassigned
	Application Filing Date: February 3, 2004	Group: Unassigned
and the second s	Information Disclosure Statement mailed:	April 24, 2004

U.S. PATENT DOCUMENTS

Examiner Initial	Copy Enclosed	Document Number	Date	Name	Class	Sabelass	Filing Date II
ar		3,968,565	07/13/76	Bertens et al.			
m	_	5,545,289	08/13/96	Chen et al.		·	
MV		5,741,368	04/21/98	Sahbari			
m		5,780,359	07/14/98	Brown et al.			
M		5,811,022	09/22/98	Savas et al.			
W		5,851,302	12/22/98	Solis			
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W.		6,162,738	12/19/00	Chen et al.			
W		6,703,319	03/09/04	Yates et al.			

FOREIGN PATENT DOCUMENTS

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Initial	Enclused		 				Yes	Nο
\mathcal{N}		0662705 A2	12/29/94	Europe				
W		0773480 A1	11/13/96	Europe				
M		411067703	03/9/99	Japan		-		
N		WO 99/45443	09/10/99	PCT				

OTHER DOCUMENTS (Including Authors, Title, Date, Pertinent Papers, etc.)

Examiner Initia)	Copy Enclosed	Document Description
w		"Material Safety Data Sheet for PRX-407®", Silicon Valley Chemlabs, Inc., Sunnyvale, VA 94086, 1998:4 pgs.

EXAMINER	Date C nsidered
Jun	6/19/66
*Examiner: Initial If citation considered, whether or not citation is conformance and not considered. Jet but copy of this form with a	in conformance with ATPEP 609: Draw line through citation if not in ext communication to applicant.

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DISCLOSURE STATEMENT	Applicant(s): Yates et al.	Confirmation N .: Unassigned
	Application Filing Date: February 3, 2004	Group: Unassigned
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"Material Safety Data Sheet", Shipley, PRX-407 Advanced Plasma Etch I Remover, July 26, 2000:7 pgs. Product information for: PRX-407® Advanced Plasma Etch Polymer Rem Silicon Valley Chemlabs, Inc., Sunnyvale, CA 94086, 1998 "Post-Etch SWP Removal," SVC Silicon Valley Chemlabs, Inc., Sunnyvale, 94086:5 pgs.	
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EXAMINER	Date Considered	
Alm.	6/19/06	
*Examiner: Initial if clinton considered, whether ur not citation conformance and not considered. Include copy of this form with	n is to conformance with MPEP 609/ Draw line through citation if not in post communication to applicant.	